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Strain-induced properties of epitaxial VOx thin films

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Publications

A. D. Rata, V. Kataev, D. Khomskii, and T. Hibma, *Giant positive magnetoresistance in metallic VO_x thin films*, accepted for publication in Phys. Rev. B (R).

A. D. Rata, A. R. Chezan, T. Hibma, M. W. Haverkort, L. H. Tjeng, H. H. Hsieh, H.-J. Lin, and C. T. Chen, *Growth and properties of strained VO_x thin films with controlled stoichiometry*, accepted for publication in Phys. Rev. B.

A. D. Rata, A. Chezan, C. Presura, and T. Hibma, *Electrical properties of VO_x thin films*, Surf. Sci. **532-535**, 341 (2003).

A. D. Rata, S. Vongtragool, D. O. Boerma, and T. Hibma, *Stoichiometry determination of VO_x thin films by $^{18}O_2$ - RBS spectrometry*, Thin Solid Films **400**, 120 (2001).

D. J. Huang, L. H. Tjeng, J. Chen, C. F. Chang, W. P. Wu, A. D. Rata, T. Hibma, S. C. Chung, S. G. Shyu, C. C. Wu, and C. T. Chen, *Electron correlation effects in half-metallic transition metal oxides*, Surf. Rev. Lett. **9**, 1007 (2002).

D. J. Huang, C. F. Chang, J. Chen, L. H. Tjeng, A. D. Rata, W. P. Wu, S. C. Chung, H. J. Lin, T. Hibma, and C. T. Chen, *Spin-resolved photoemission studies of epitaxial $Fe_3O_4(100)$ thin films*, J. Magn. Mag. Mat. **239**, 261 (2002).

A. D. Rata and T. Hibma, *Strain induced properties of epitaxial VO_x thin films*, to be submitted.

A. D. Rata, C. Presura, I. Elfimov, L. H. Tjeng, and T. Hibma, *Direct measurement of a band gap in near stoichiometric VO*, to be submitted.

